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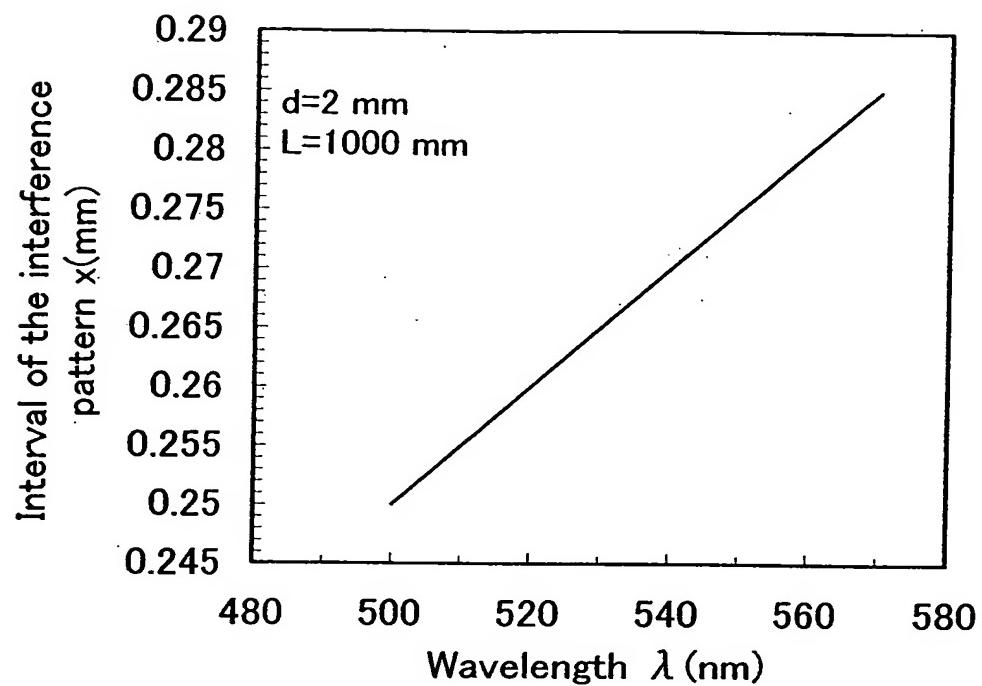


FIG. 1

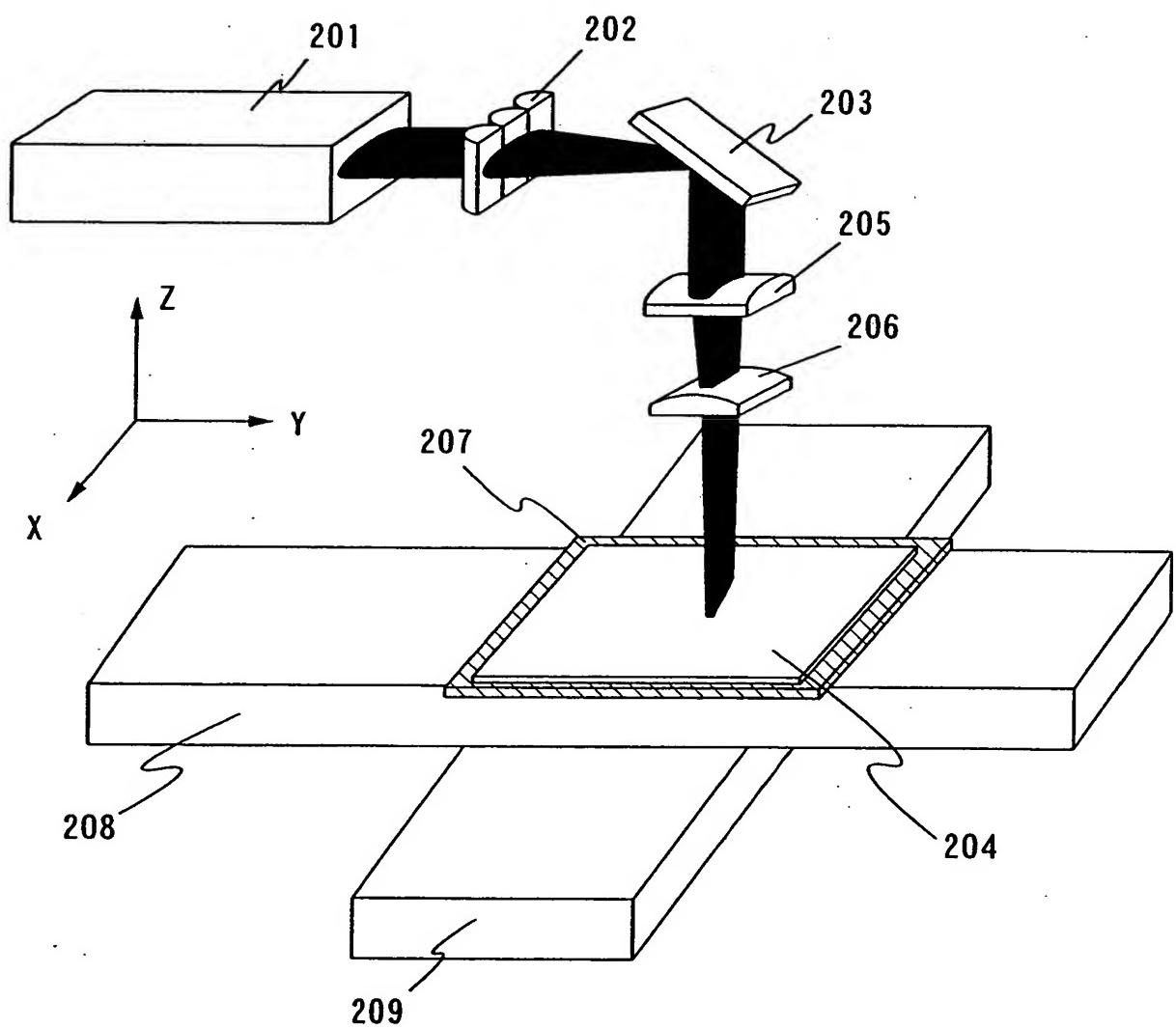


FIG. 2

FIG. 3-(1)

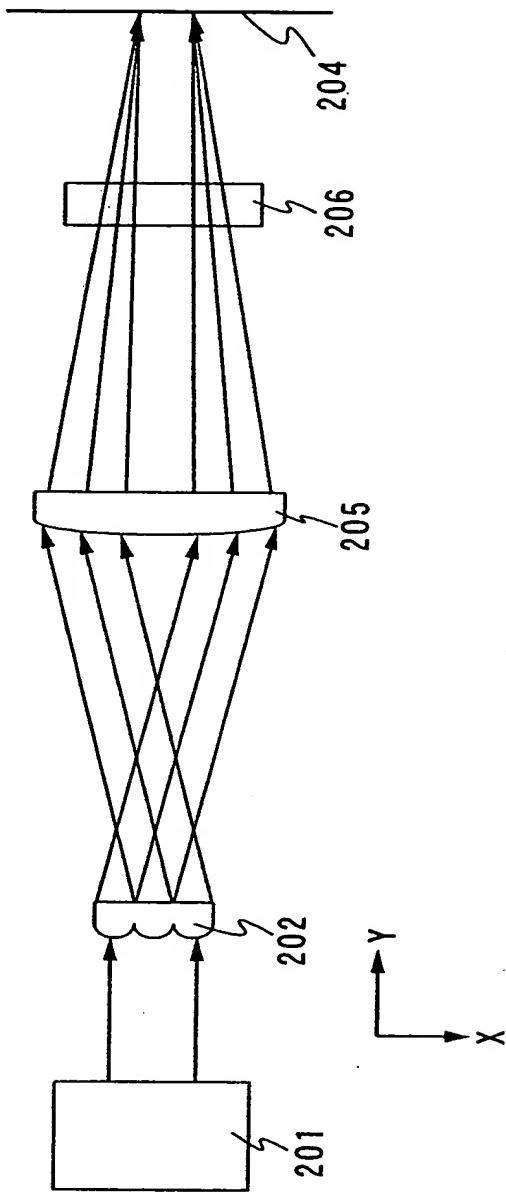
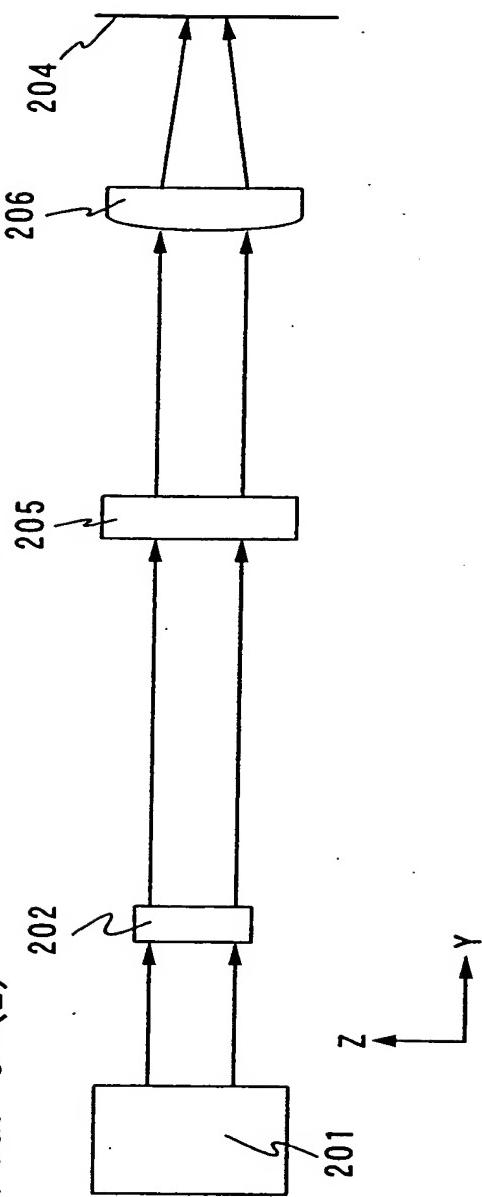


FIG. 3-(2)



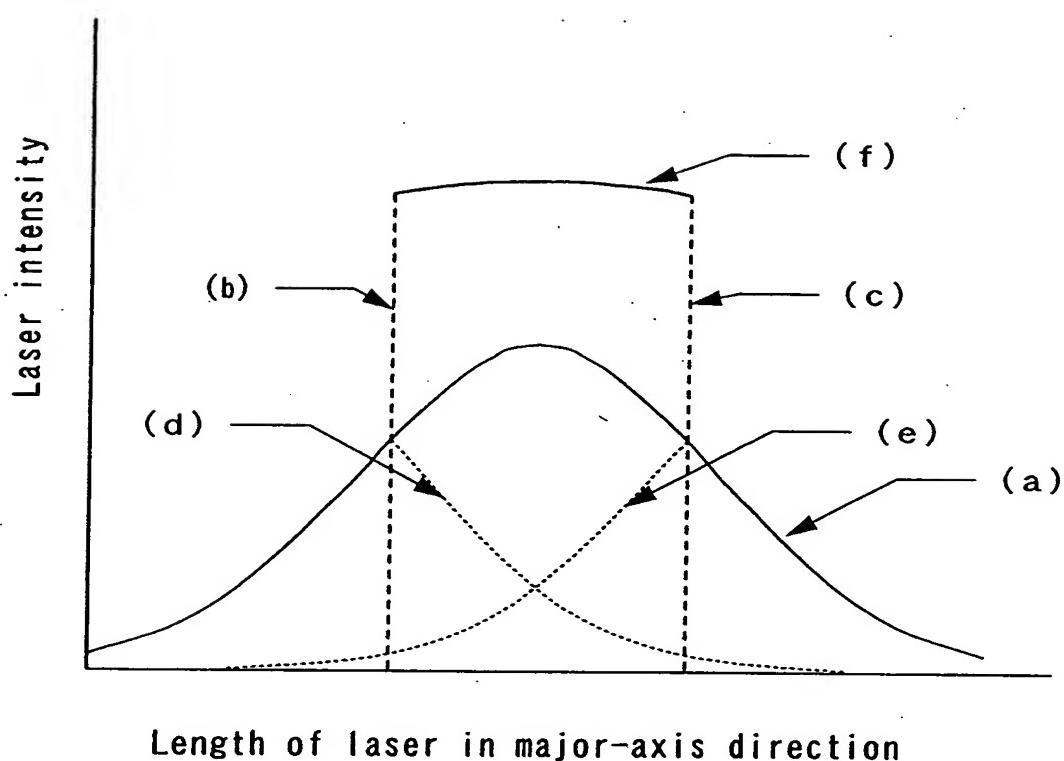


FIG. 4

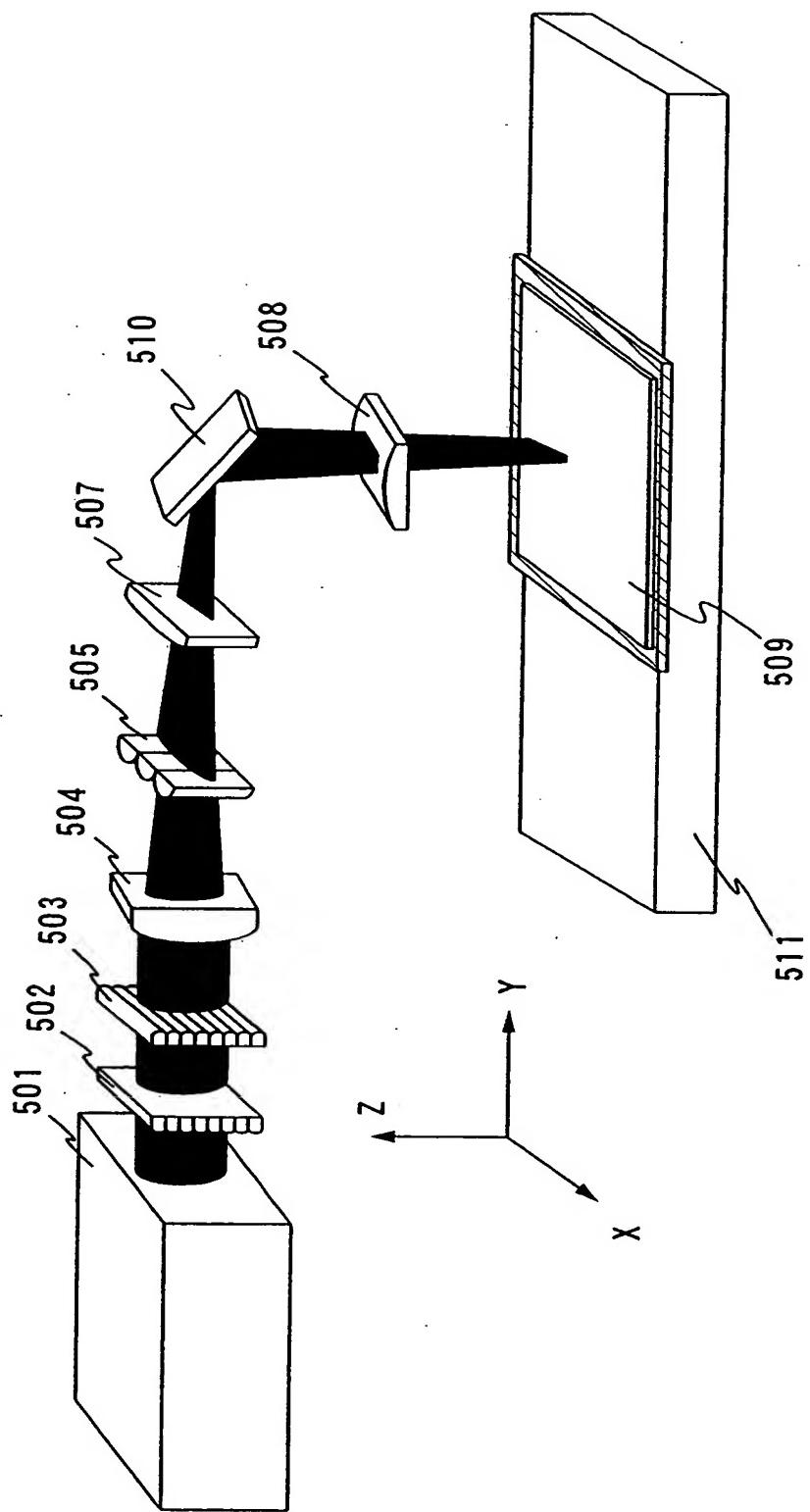


FIG. 5

FIG. 6-(1)

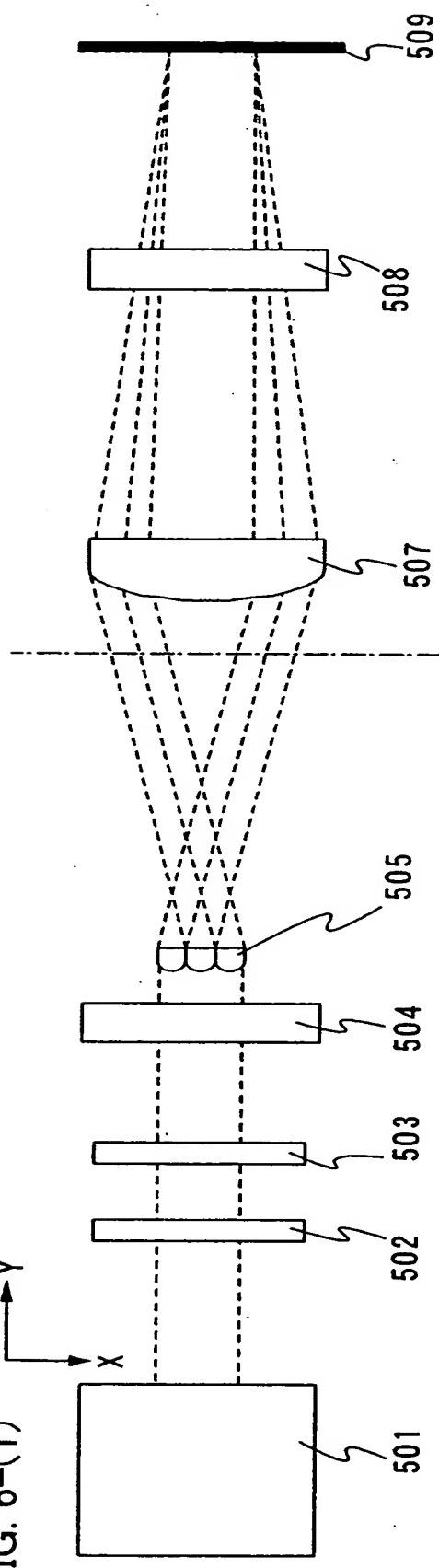


FIG. 6-(2)

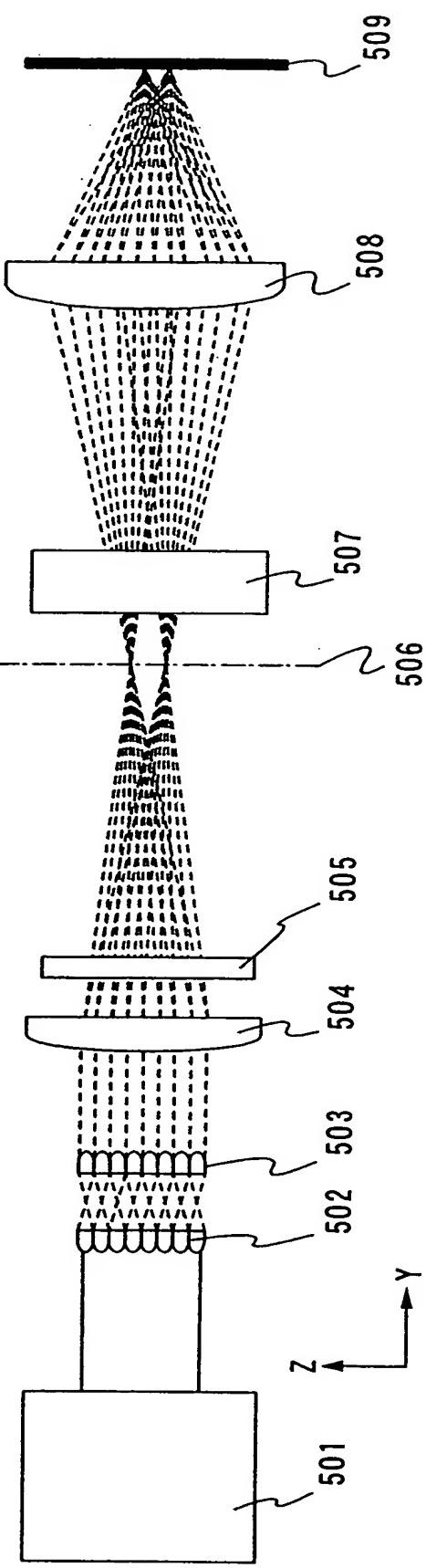


FIG. 7A

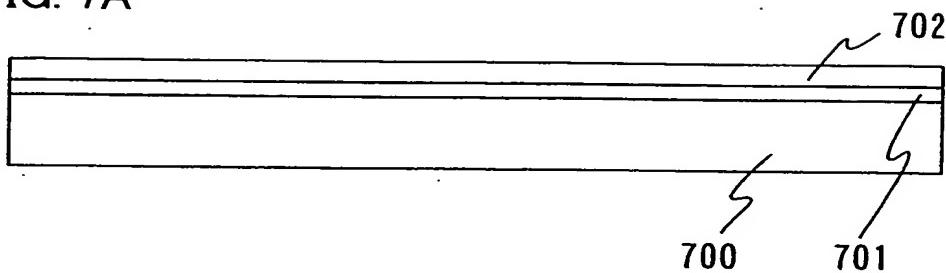


FIG. 7B

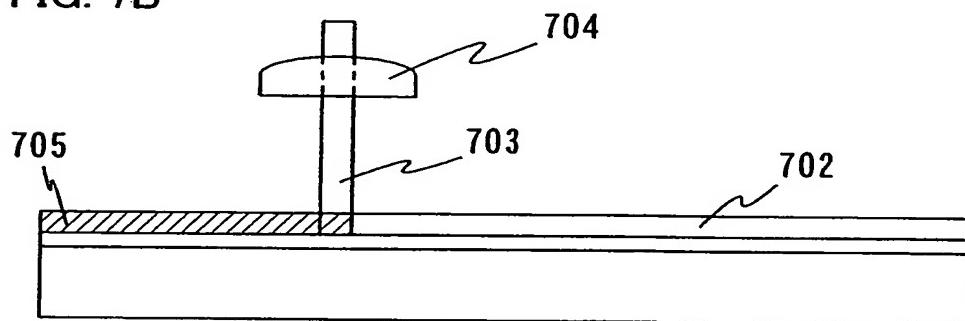


FIG. 7C

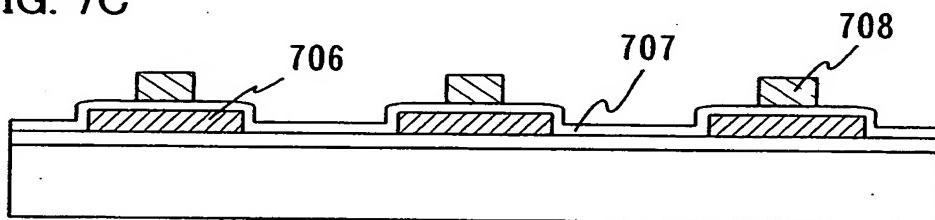
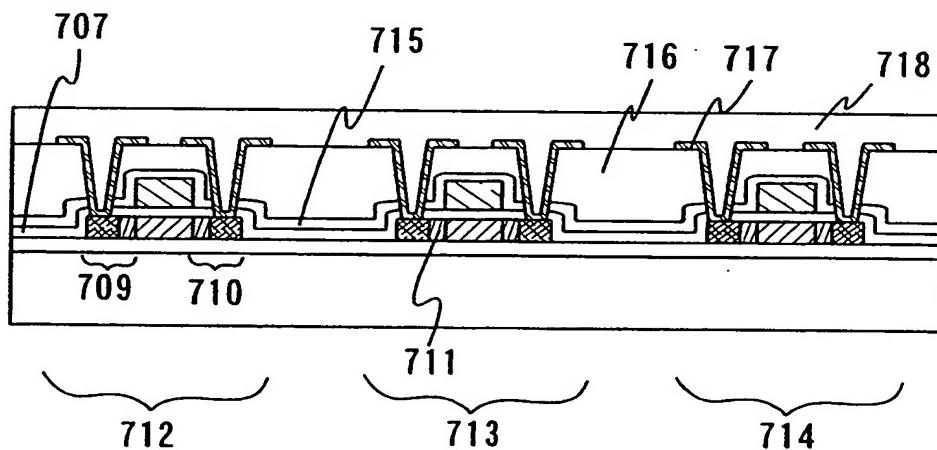


FIG. 7D



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FIG. 8A

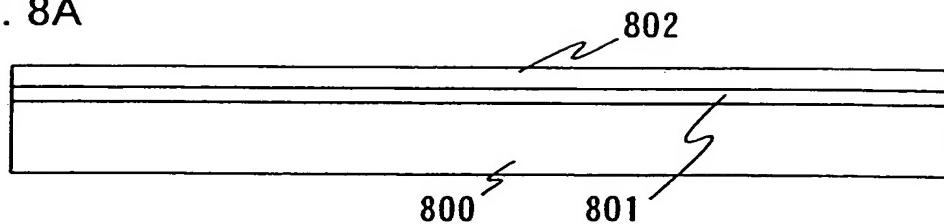


FIG. 8B

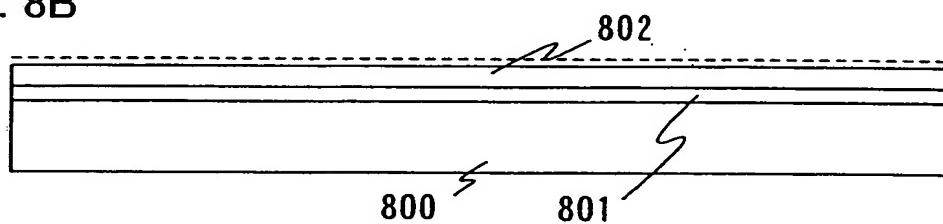


FIG. 8C

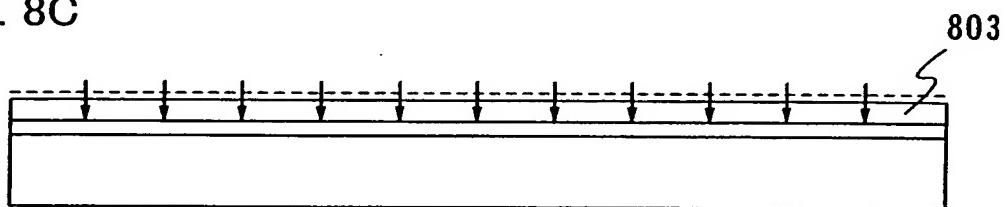
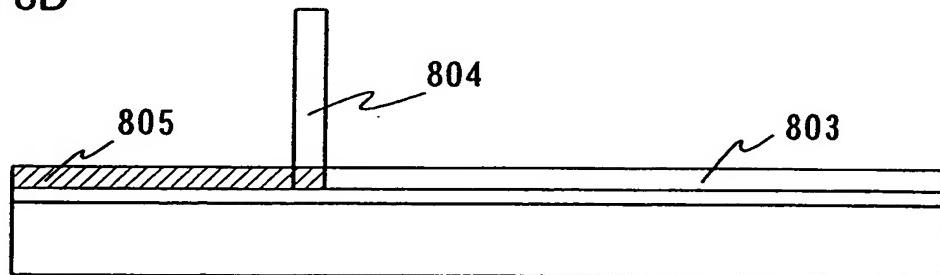


FIG. 8D



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FIG. 9A

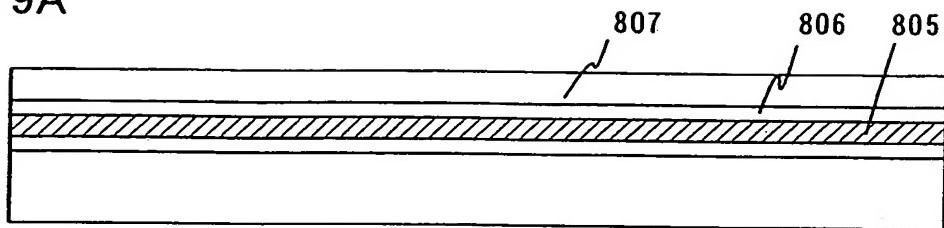


FIG. 9B

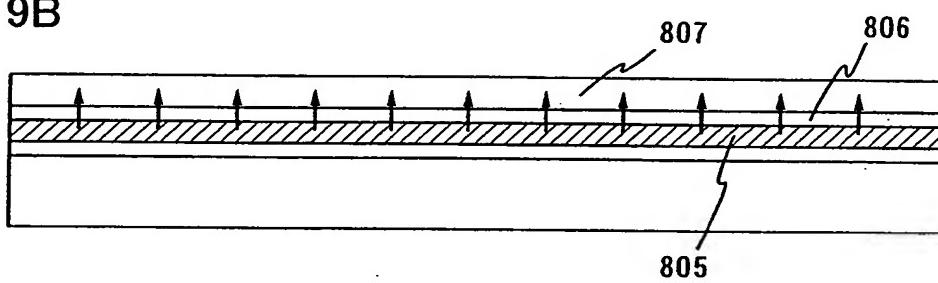
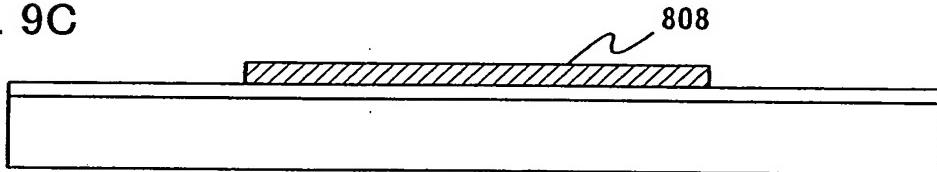
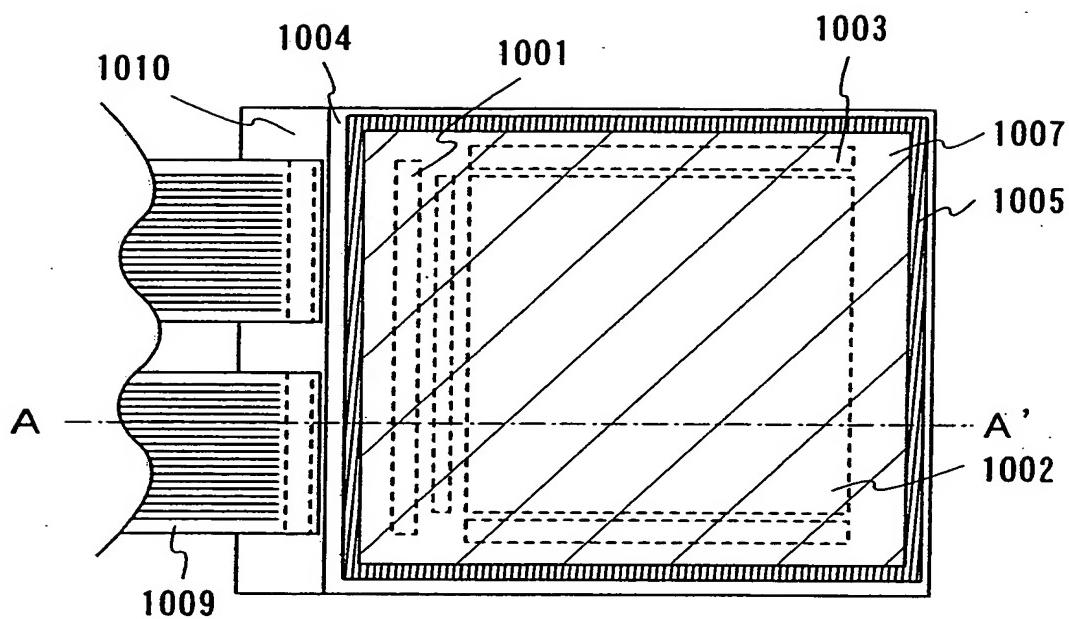


FIG. 9C



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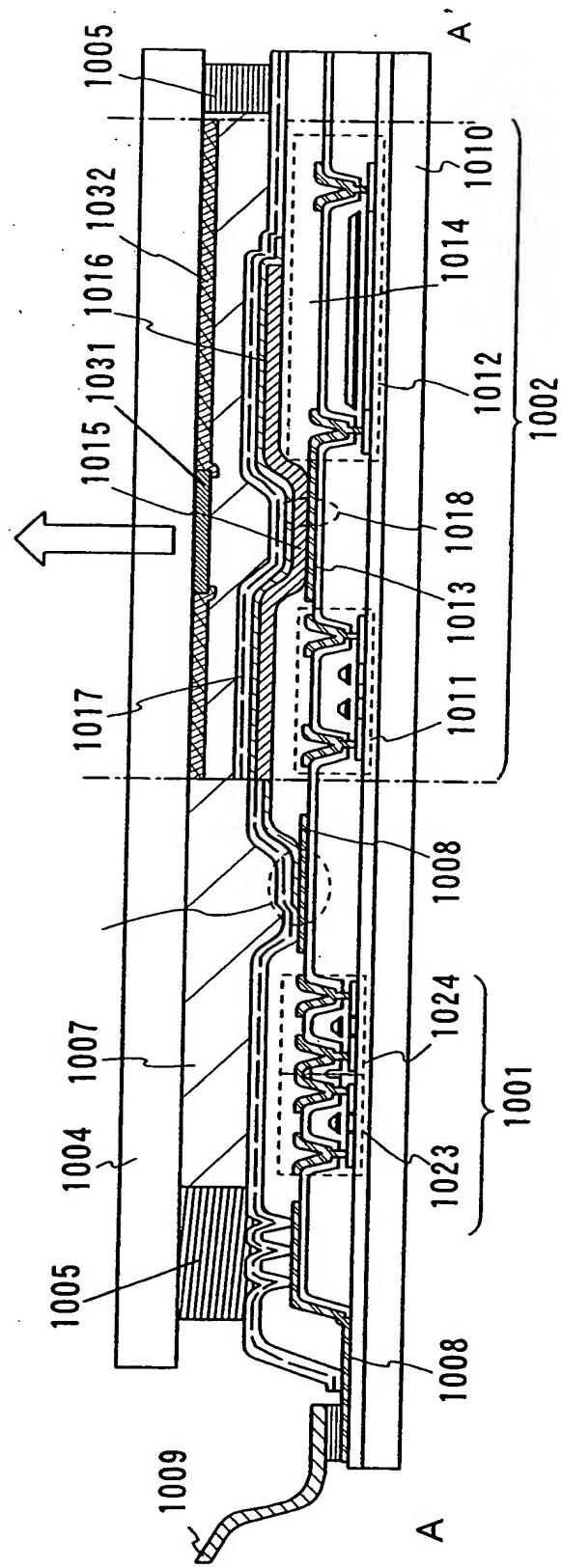


FIG. 11

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FIG. 12A

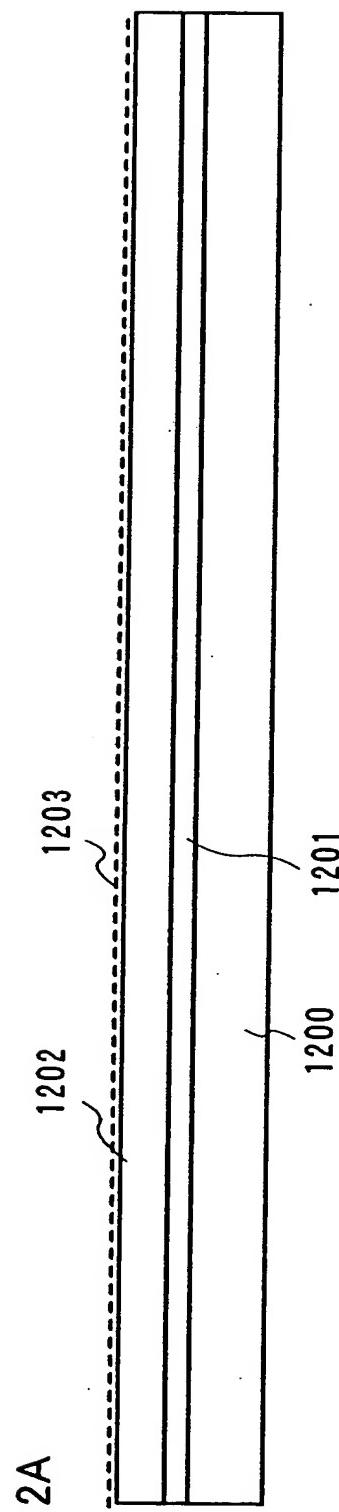


FIG. 12B

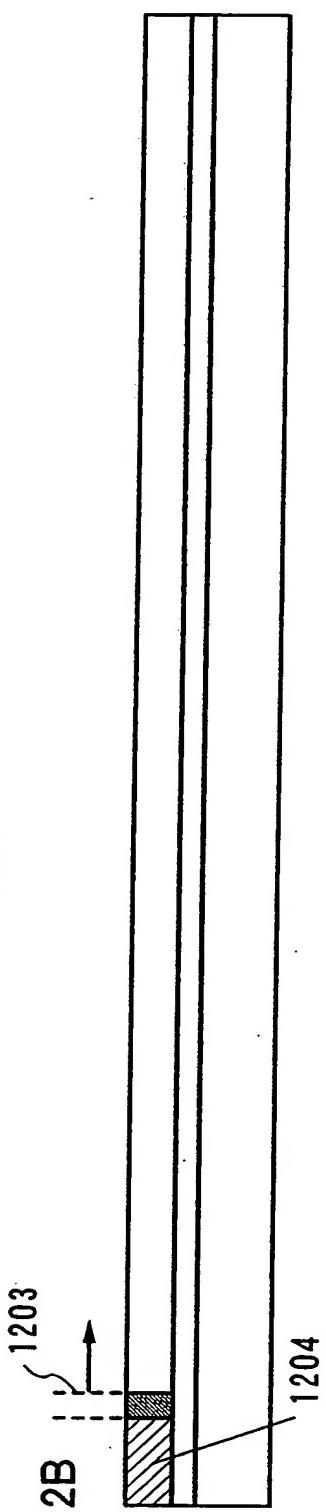


FIG. 12C

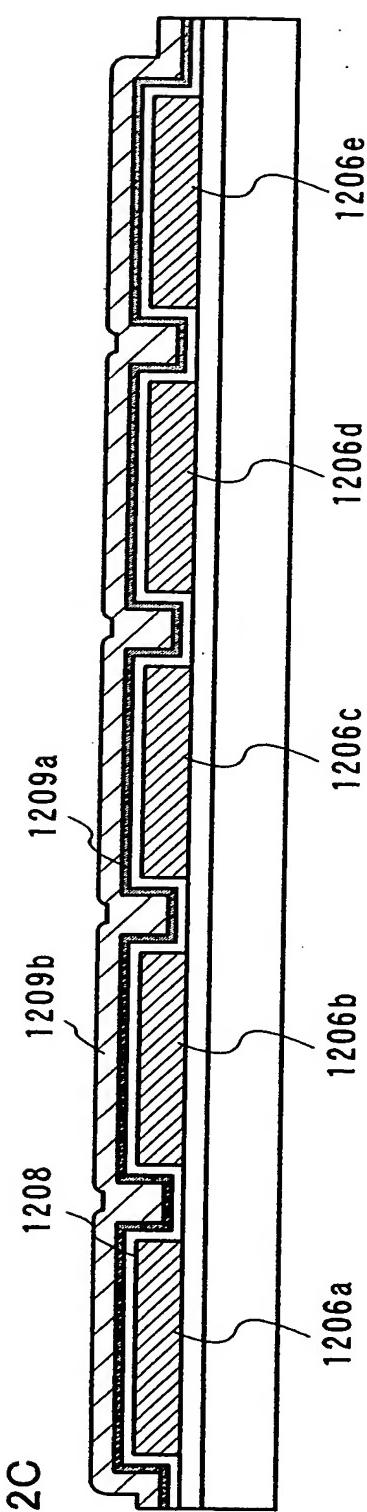


FIG. 13A

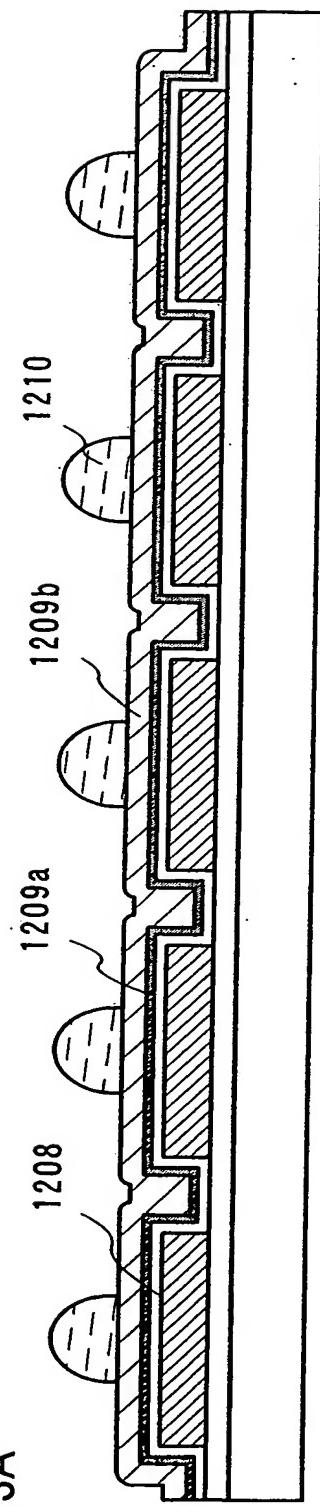


FIG. 13B

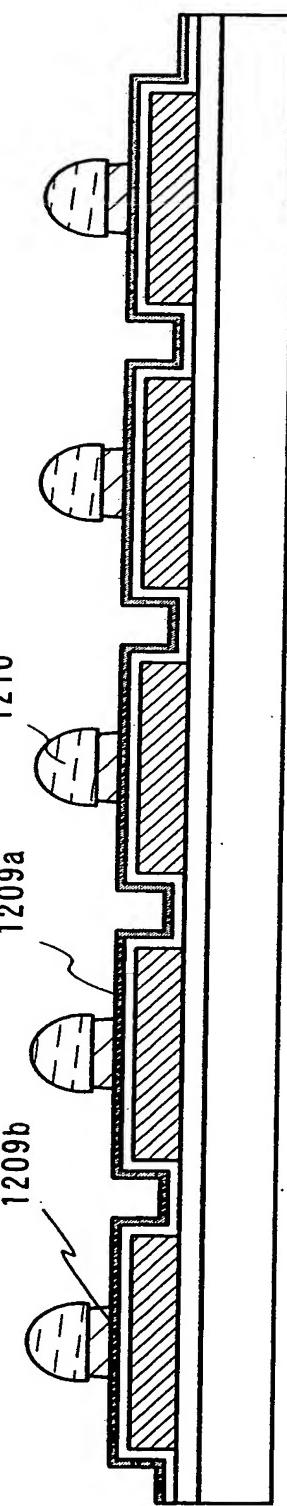


FIG. 13C

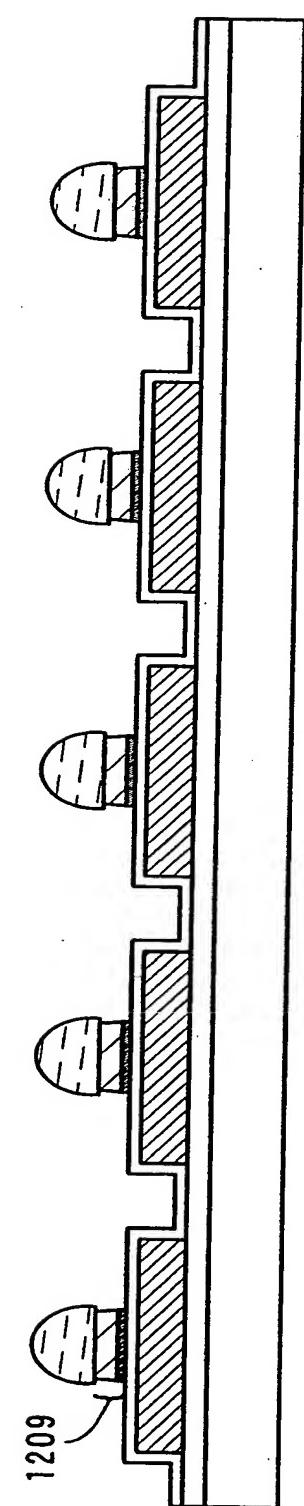


FIG. 14A

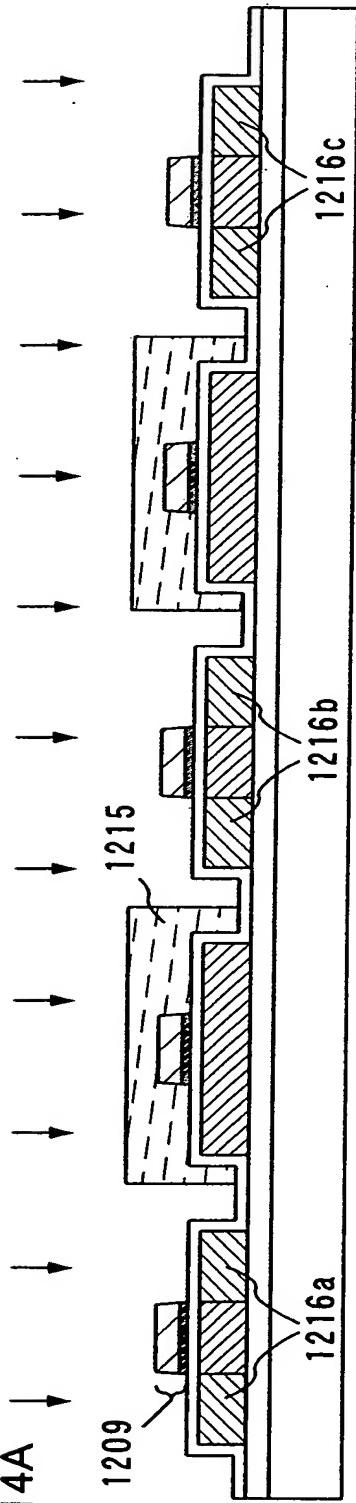


FIG. 14B

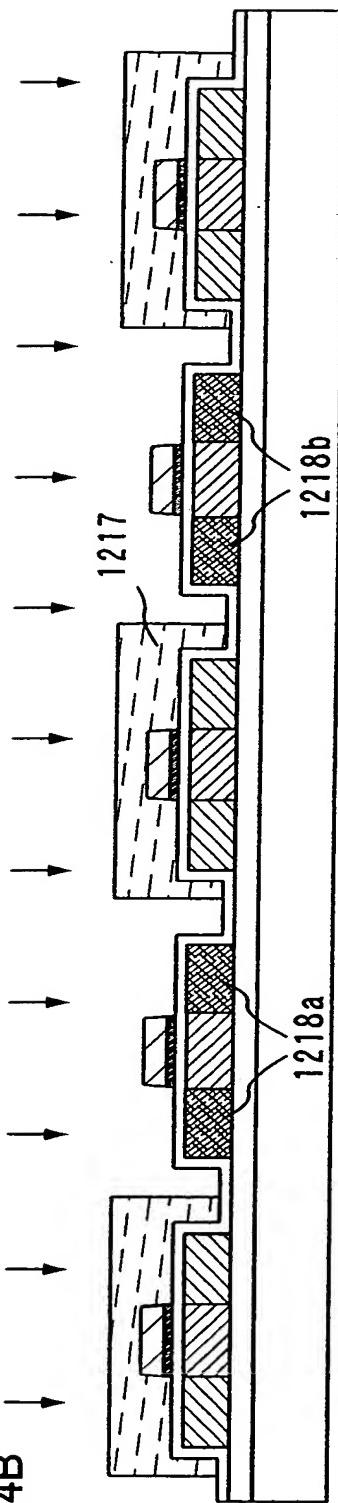


FIG. 14C

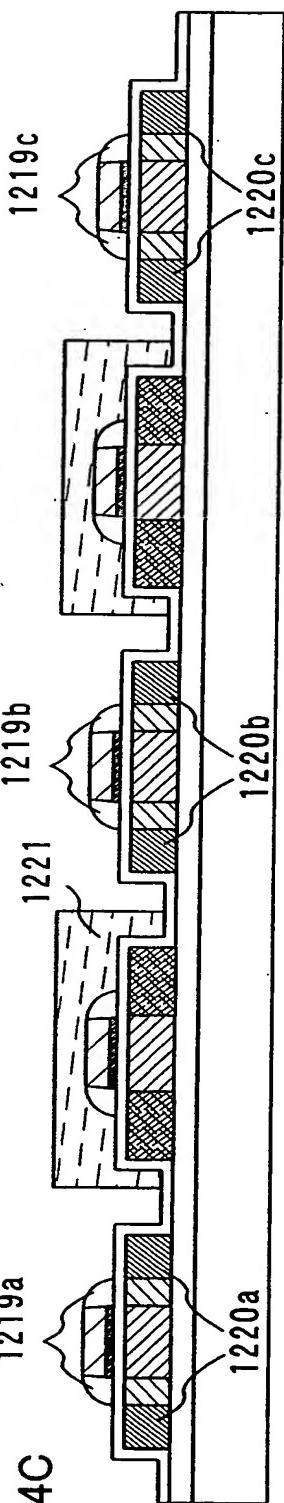


FIG. 15A

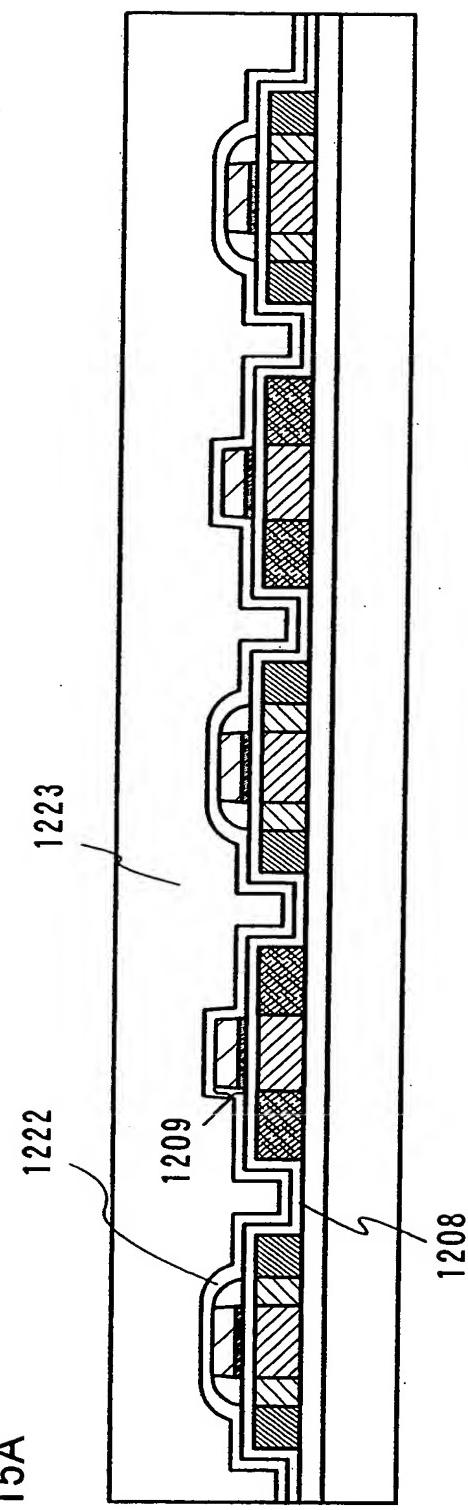
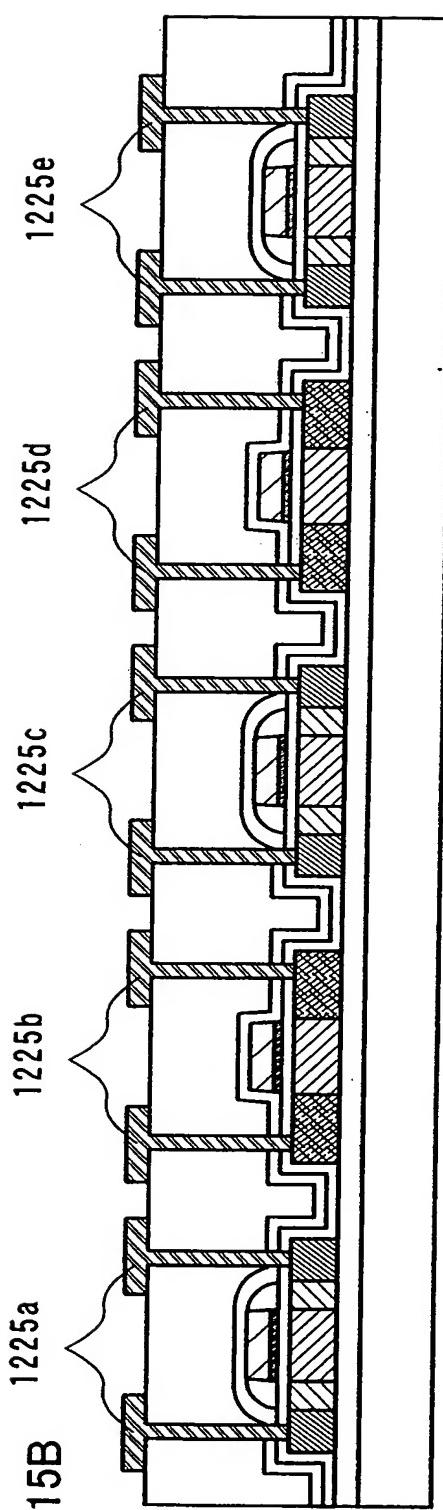


FIG. 15B



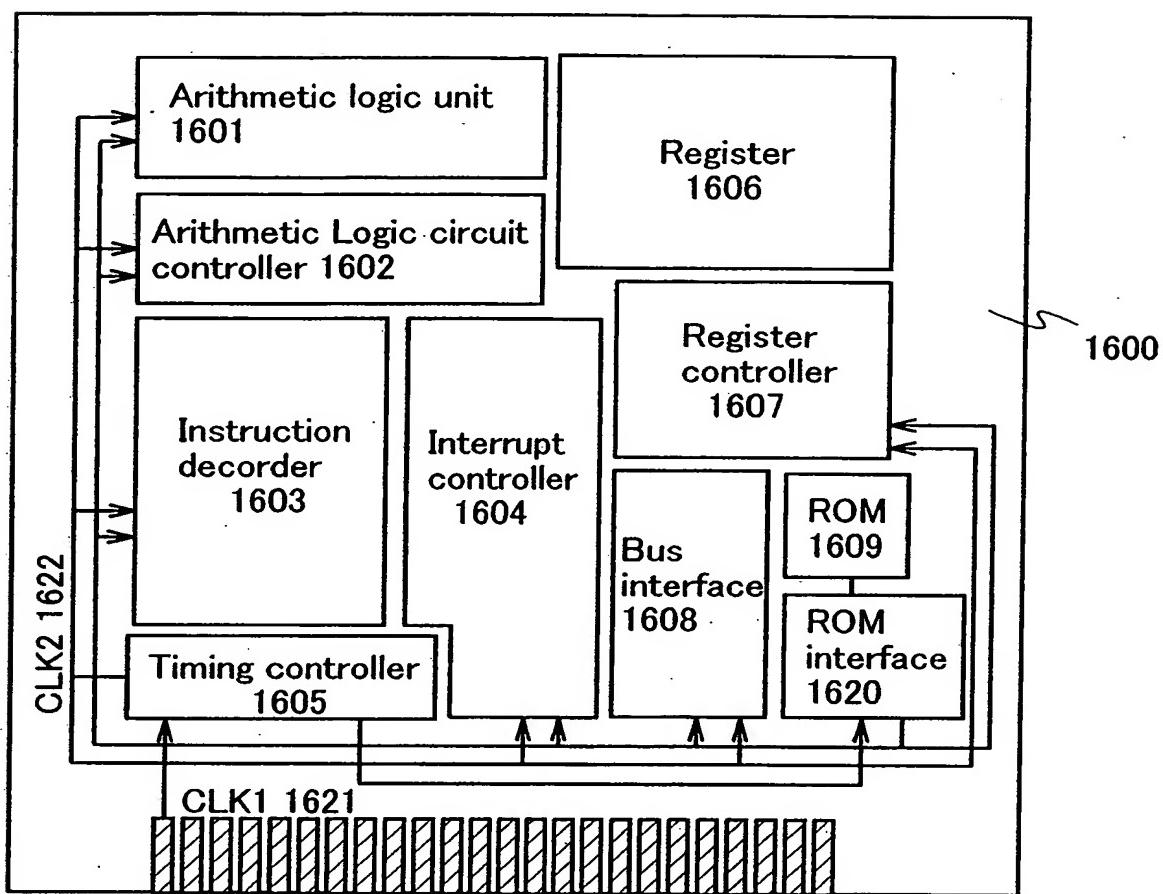


FIG. 16

FIG. 17A

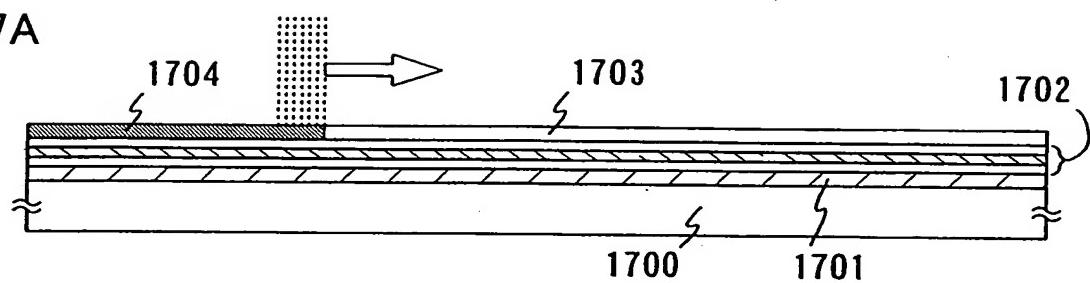


FIG. 17B

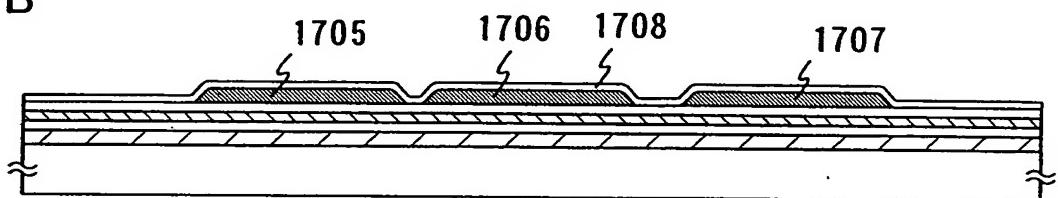


FIG. 17C

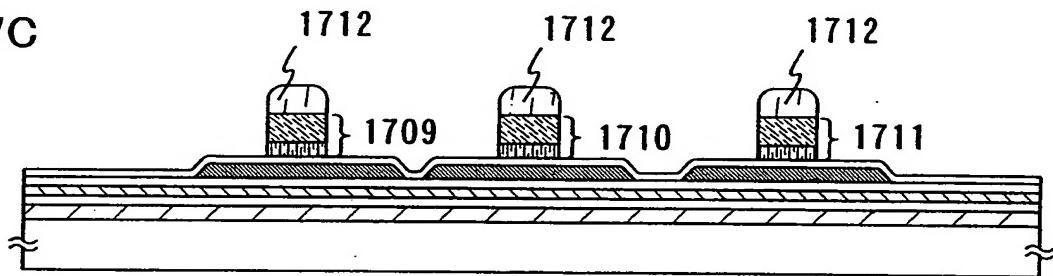


FIG. 17D ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓

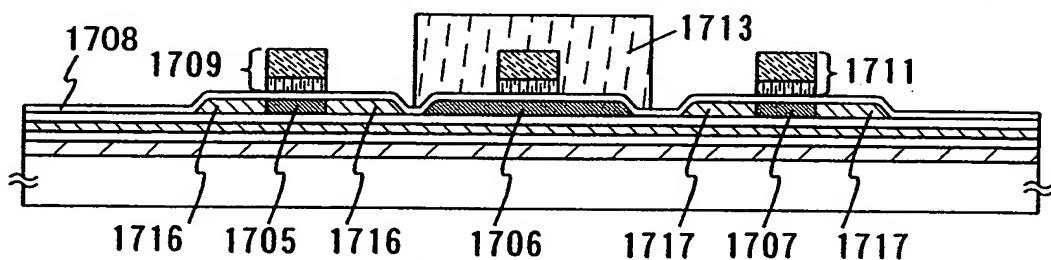


FIG. 17E ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓

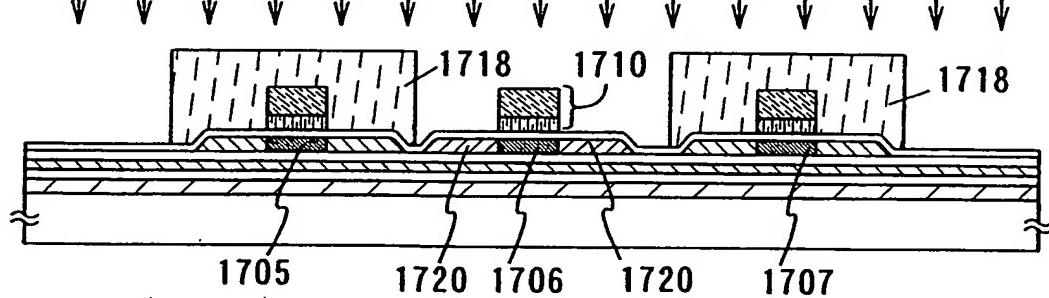


FIG. 18A

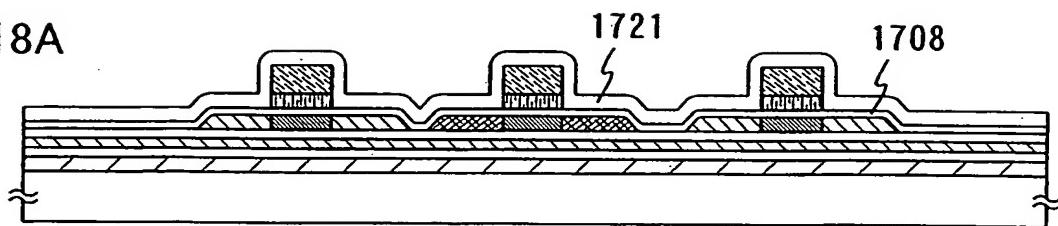


FIG. 18B

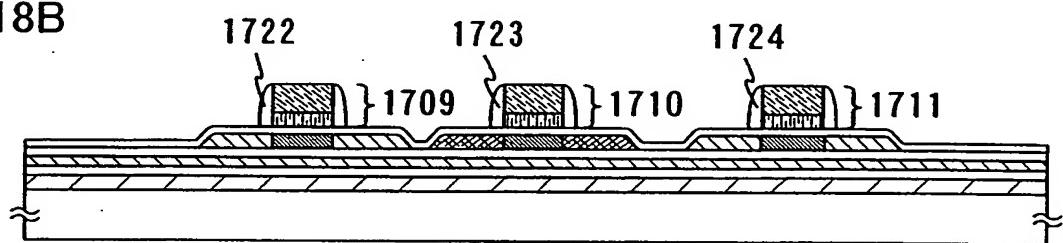


FIG. 18C ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓ ↓

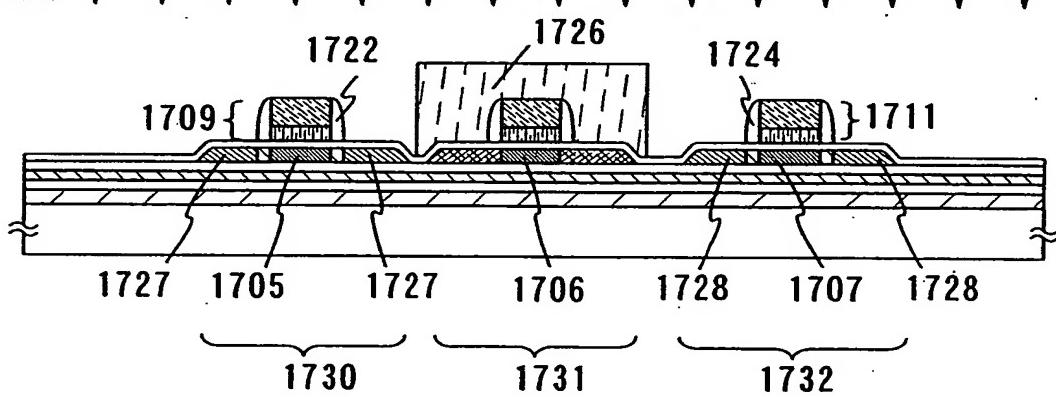


FIG. 19A

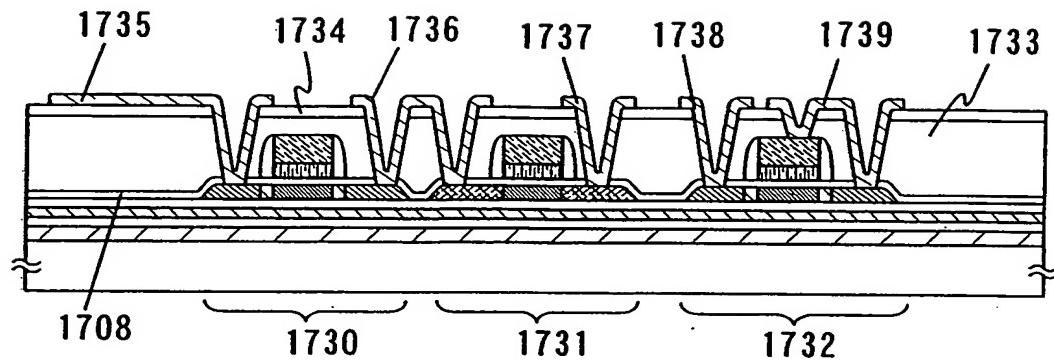


FIG. 19B

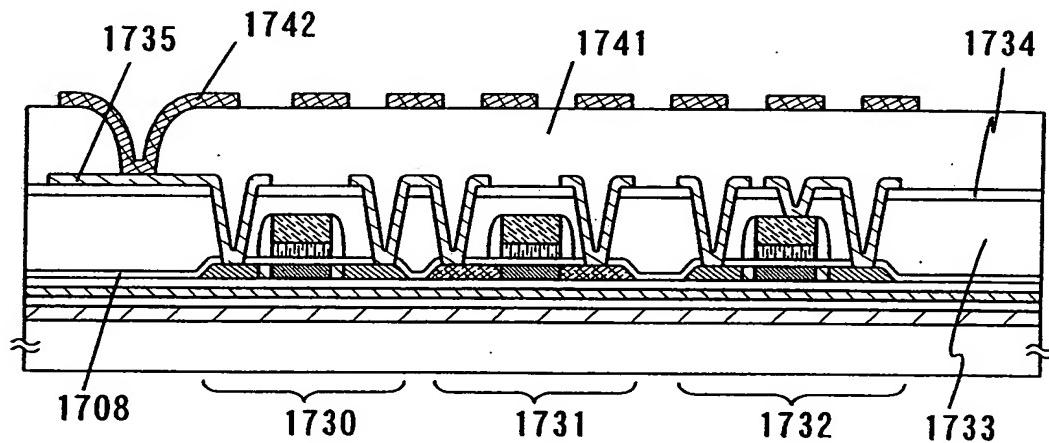


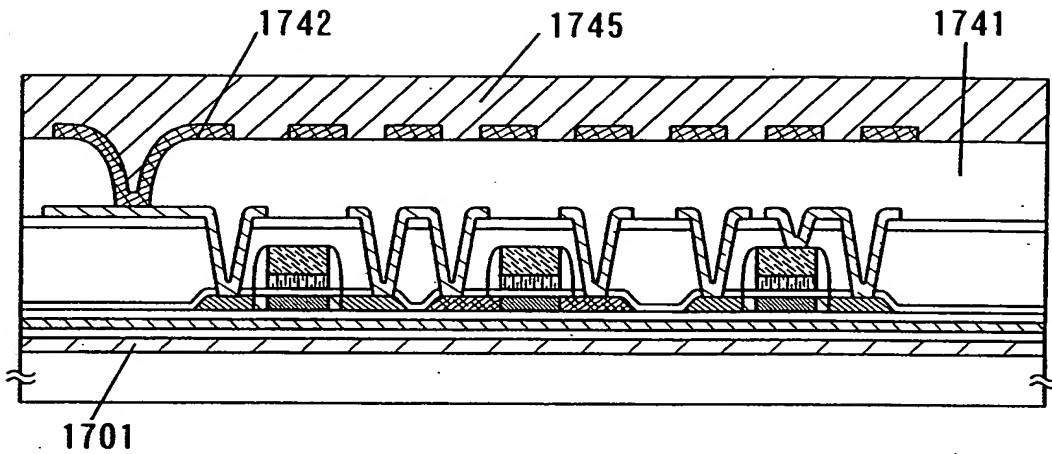
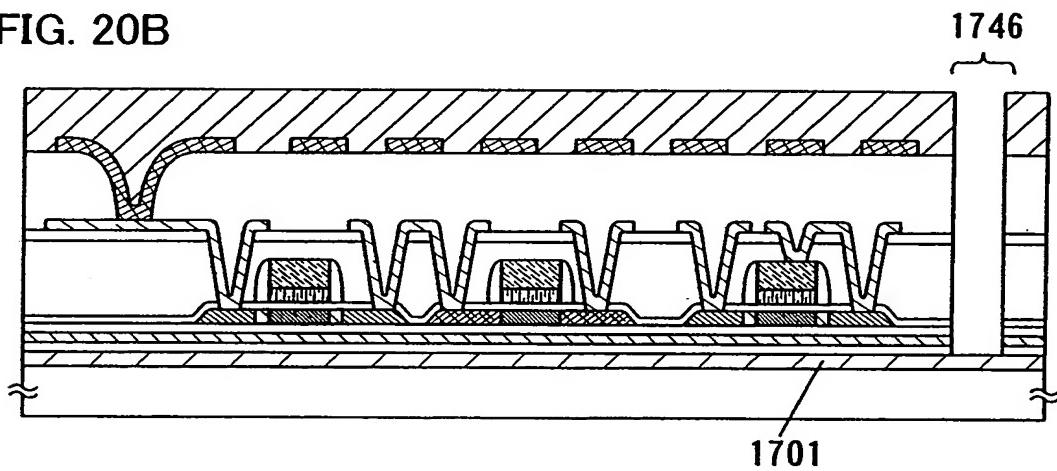
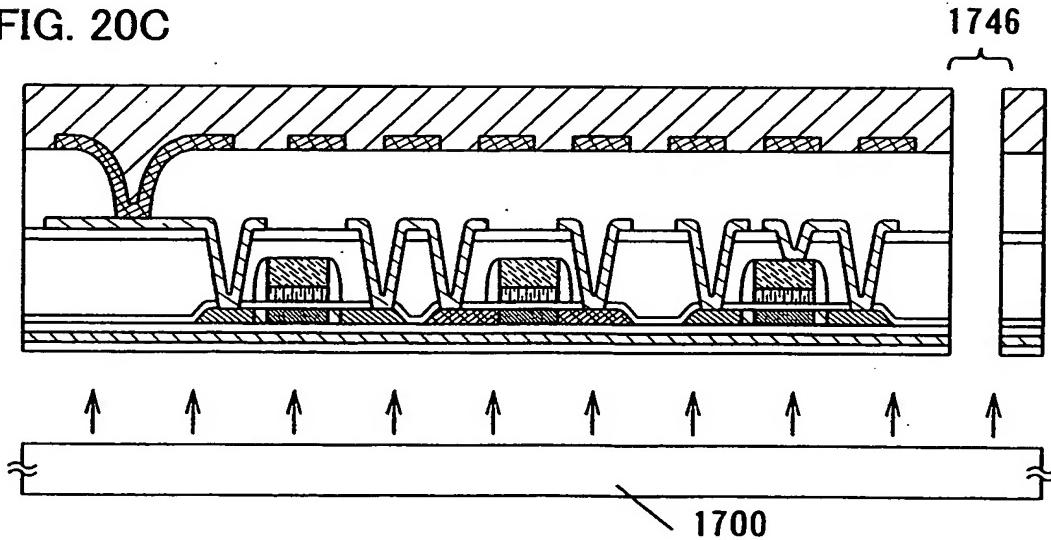
FIG. 20A**FIG. 20B****FIG. 20C**

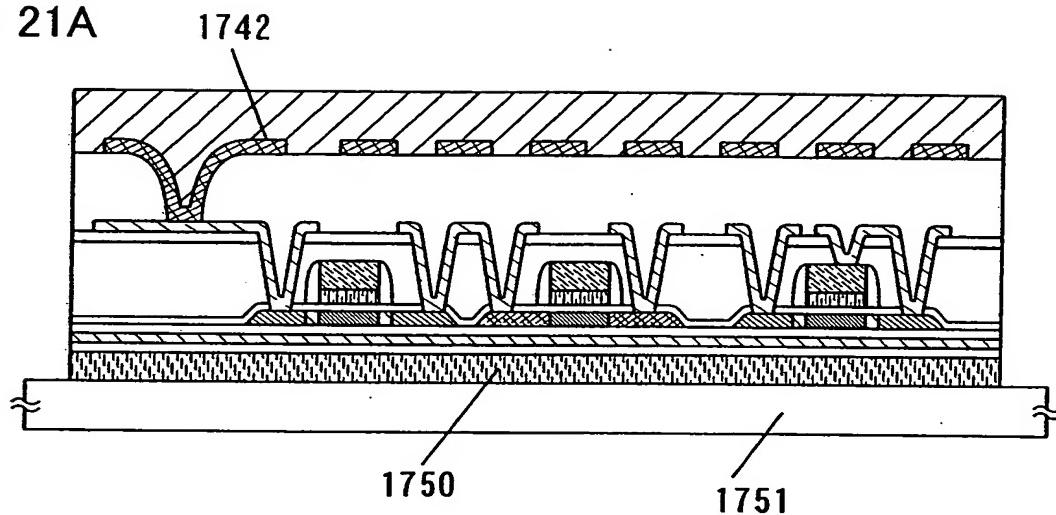
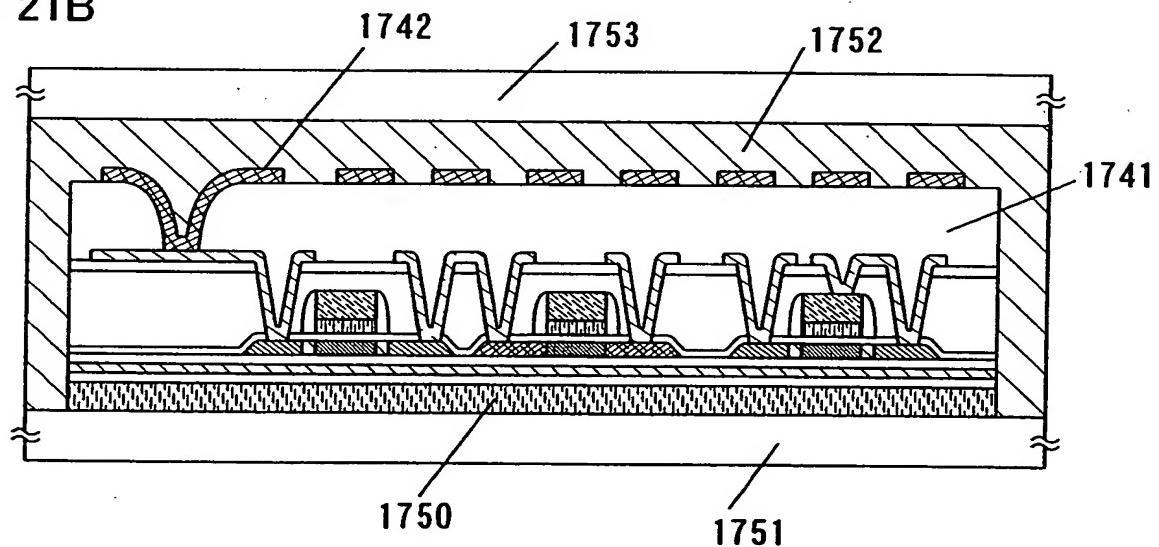
FIG. 21A**FIG. 21B**

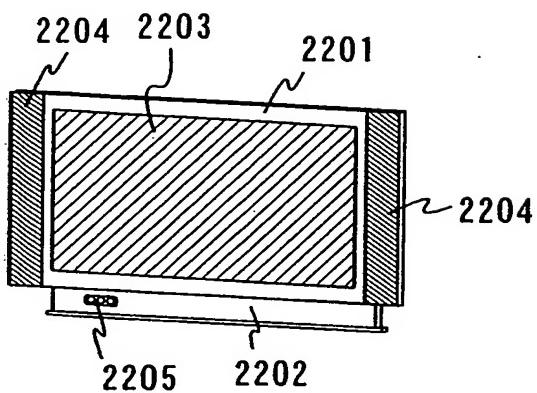
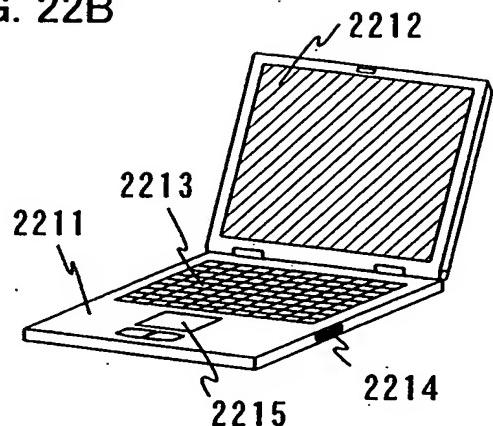
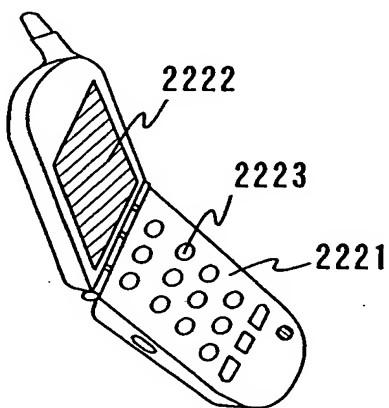
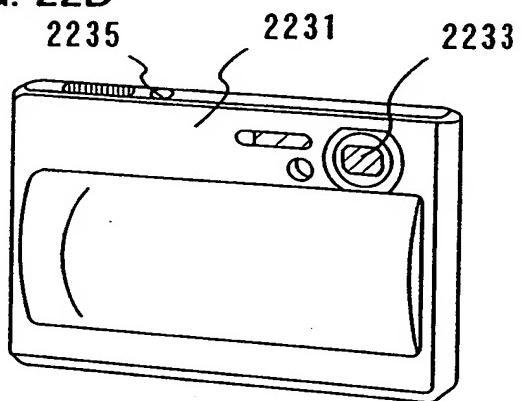
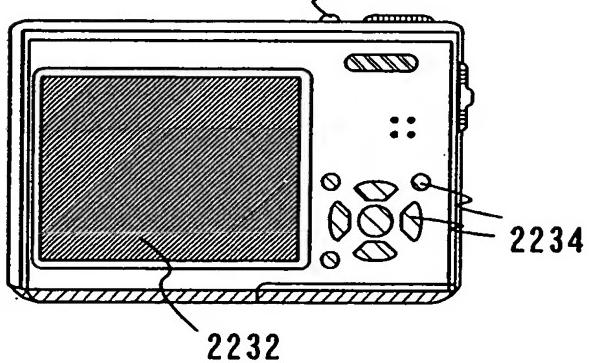
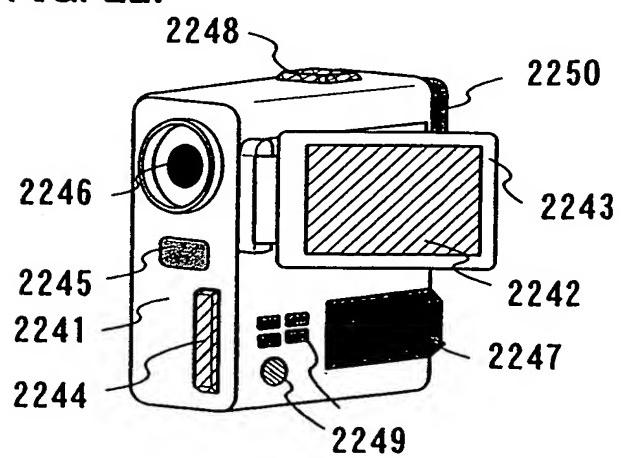
FIG. 22A**FIG. 22B****FIG. 22C****FIG. 22D****FIG. 22E 2235****FIG. 22F**

FIG. 23A

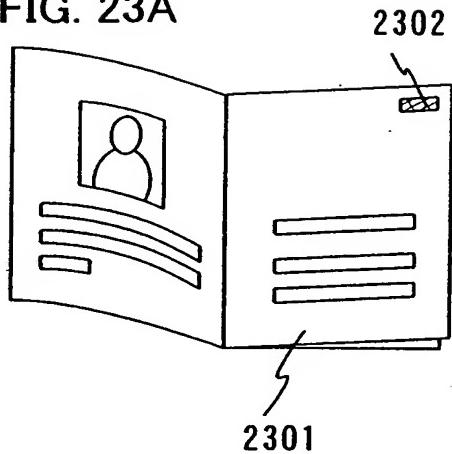
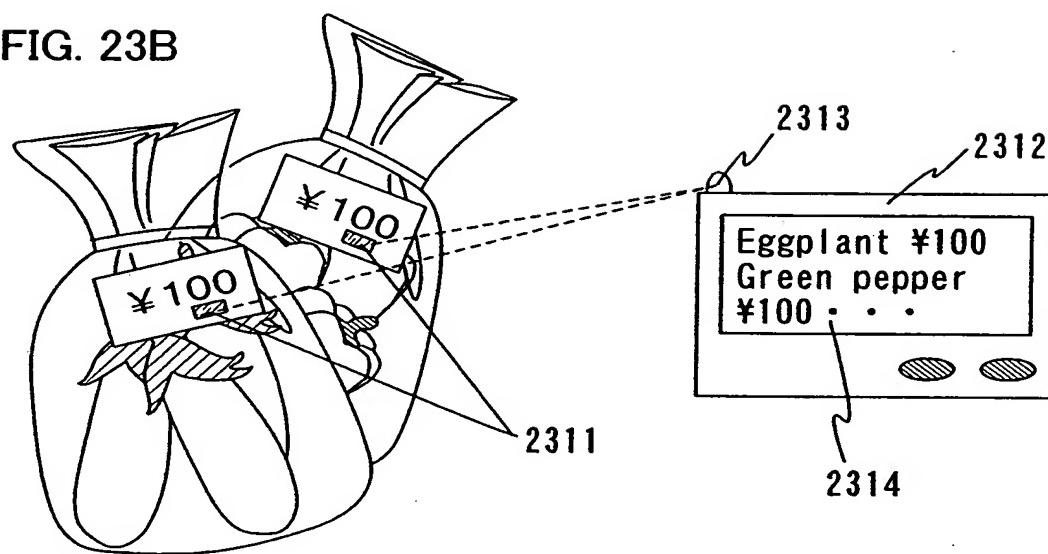
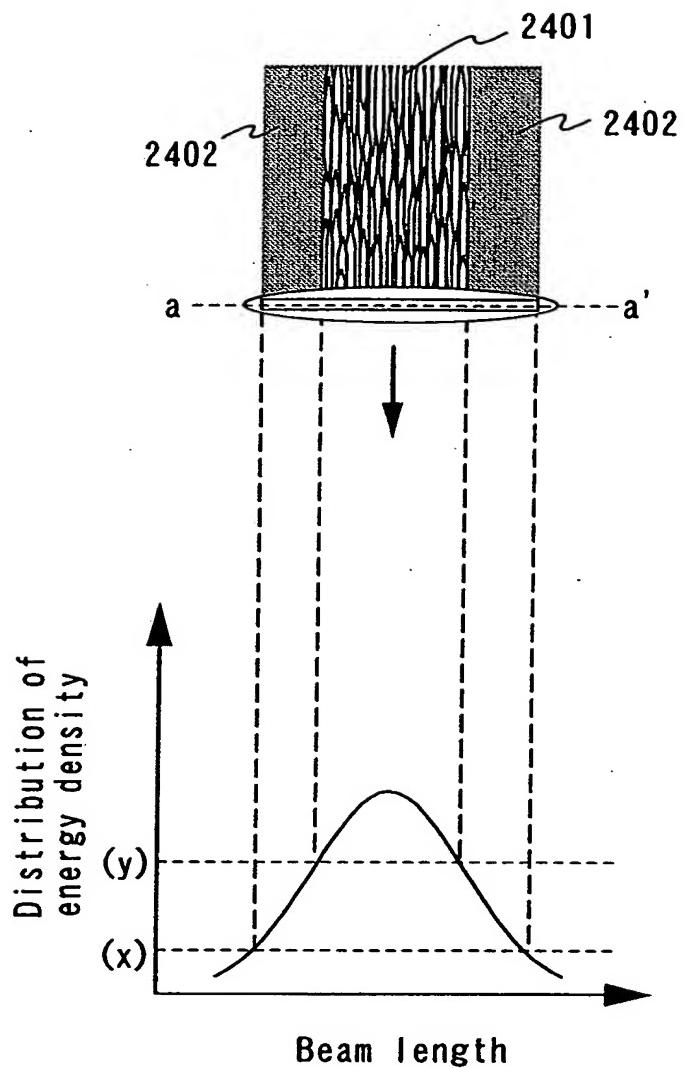


FIG. 23B





- (x) a threshold at which a crystalline region is formed
- (y) a threshold at which a large grain crystal is formed

FIG. 24

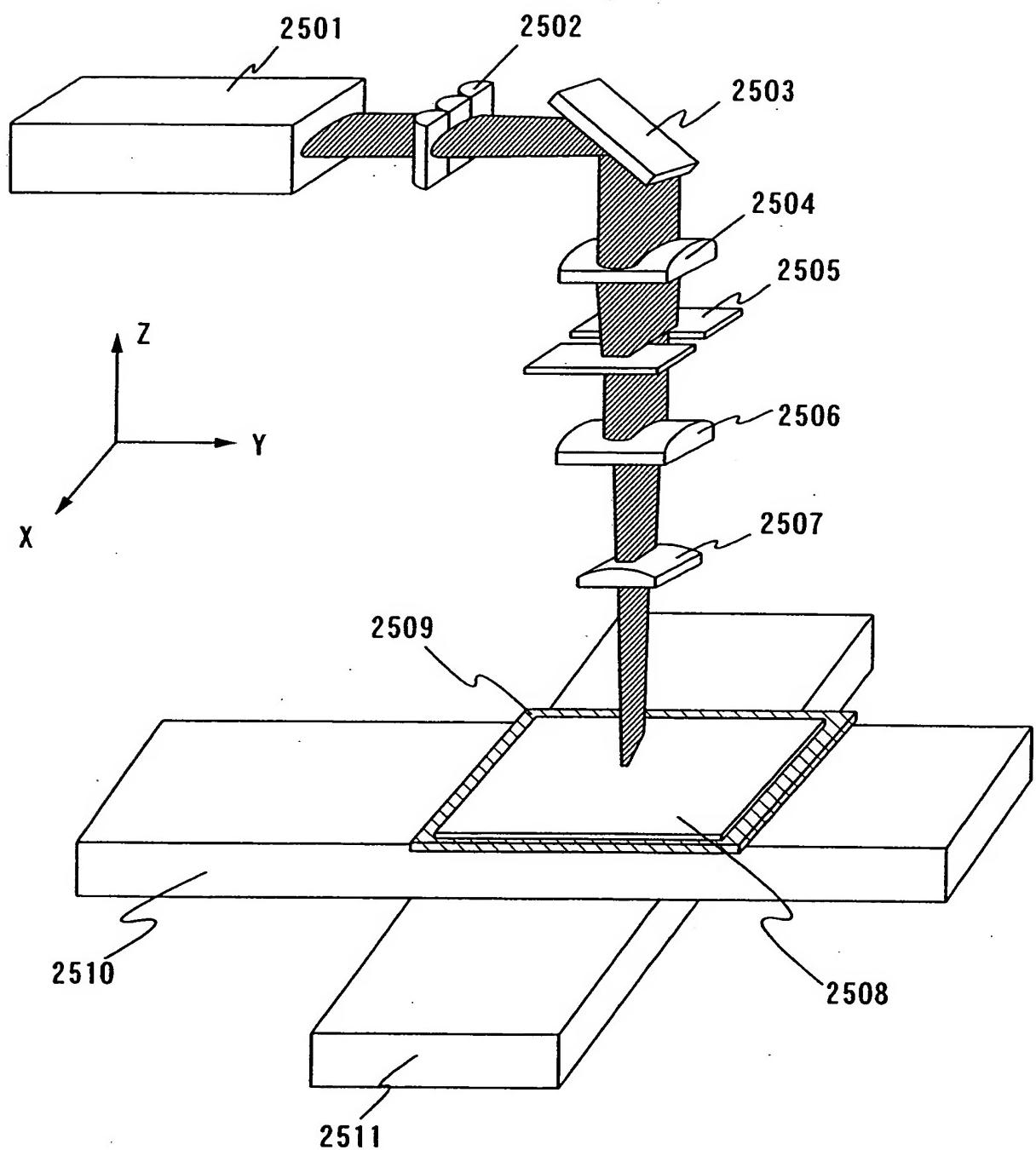


FIG. 25

Fig. 26-(1)

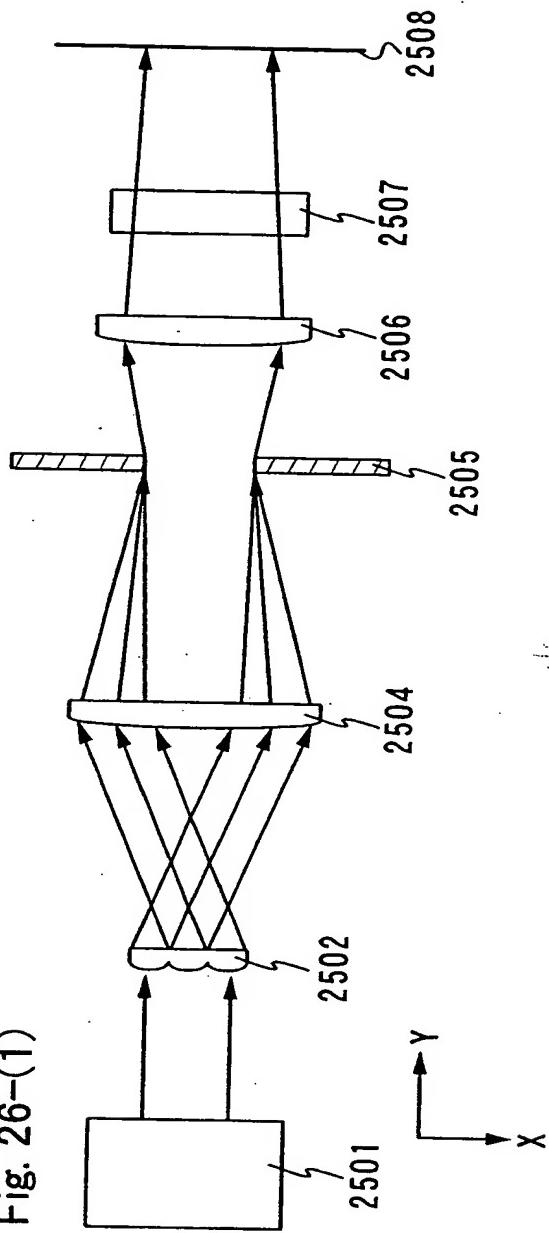
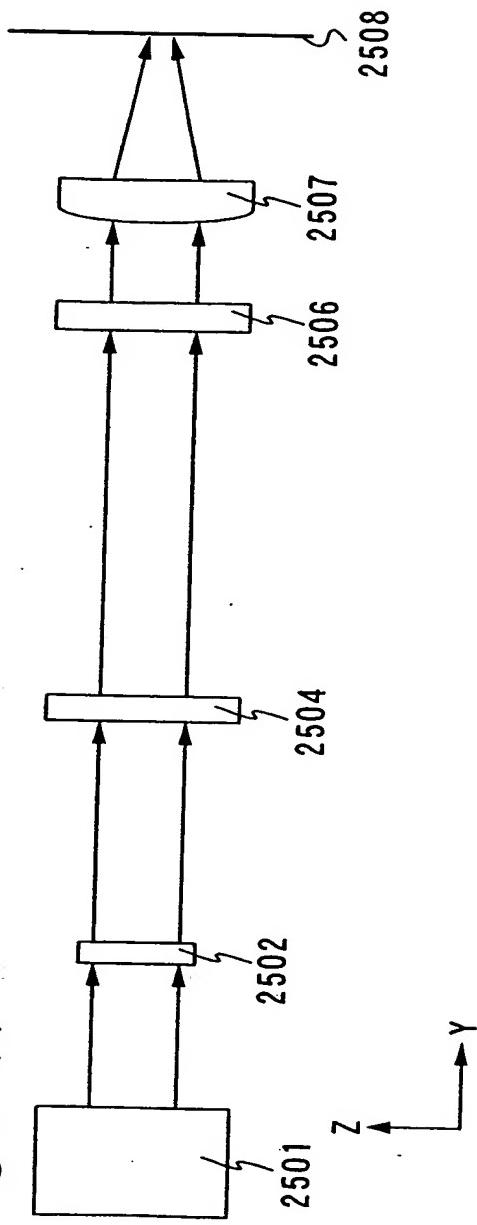


Fig. 26-(2)



EXPLANATION OF REFERENCE NUMERAL

2401: CENTRAL REGION (OF LASER BEAM), 2402: INFERIOR CRYSTALLINE REGION, 201: LASER OSCILLATOR, 202: CYLINDRICAL LENS ARRAY, 203: MIRROR, 204: SEMICONDUCTOR FILM, 205: CYLINDRICAL LENS, 206: CYLINDRICAL LENS, 207: SUCTION STAGE, 208: X STAGE, 209: Y STAGE, 501: PULSE LASER OSCILLATOR, 502: CYLINDRICAL LENS ARRAY; 503: CYLINDRICAL LENS ARRAY, 504: CYLINDRICAL LENS, 505: CYLINDRICAL LENS ARRAY, 506: PLANE, 507: CYLINDRICAL LENS, 508: CYLINDRICAL LENS, 509: SEMICONDUCTOR FILM, 510: MIRROR, 511: STAGE, 700: SUBSTRATE, 701: BASE FILM, 702: AMORPHOUS SEMICONDUCTOR FILM, 703: LASER, 704: CYLINDRICAL LENS, 705: CRYSTALLINE SEMICONDUCTOR FILM, 706: ISLAND-LIKE SEMICONDUCTOR FILM, 707: GATE INSULATING FILM, 708: GATE ELECTRODE, 709: SOURCE REGION, 710: DRAIN REGION, 711: LDD REGION, 712: N-CHANNEL TFT, 713: N-CHANNEL TFT, 714: P-CHANNEL TFT, 715: INSULATING FILM, 716: INSULATING FILM, 717: WIRING, 718: INSULATING FILM, 800: SUBSTRATE, 801: BASE FILM, 802: SEMICONDUCTOR FILM, 803: SEMICONDUCTOR FILM, 804: LASER, 805: SEMICONDUCTOR FILM, 806: OXIDE FILM, 807: SEMICONDUCTOR FILM FOR GETTERING, 808: ISLAND-LIKE SEMICONDUCTOR FILM, 1001: SOURCE SIGNAL LINE DRIVER CIRCUIT, 1002: PIXEL PORTION, 1003: GATE SIDE DRIVER CIRCUIT, 1004: SEALING SUBSTRATE, 1005: FIRST SEALING MATERIAL, 1007: SECOND SEALING MATERIAL, 1008: CONNECTION WIRING, 1009: FPC, 1010: SUBSTRATE, 1011: SOURCE SIDE DRIVER CIRCUIT, 1012: CURRENT CONTROL CIRCUIT, 1013: FIRST ELECTRODE, 1014: INSULATOR, 1015: ELECTROLUMINESCENT LAYER, 1016: SECOND ELECTRODE, 1017: TRANSPARENT PROTECTIVE LAYER, 1018: ELECTROLUMINESCENT ELEMENT, 1023: N-CHANNEL TFT, 1024: P-CHANNEL TFT, 1031: COLORED LAYER, 1032: LIGHT-SHIELDING LAYER, 1200: SUBSTRATE, 1201: BASE INSULATING FILM, 1202: AMORPHOUS SEMICONDUCTOR FILM, 1203: LASER, 1204: SEMICONDUCTOR FILM HAVING CRYSTAL STRUCTURE, 1206a to 1206e: SEMICONDUCTOR FILM, 1208: GATE INSULATING FILM, 1209a and 1209b:

CONDUCTIVE FILM, 1210: RESIST MASK, 1215: RESIST MASK, 1216a to 1216c: IMPURITY REGION, 1217: RESIST MASK, 1218a and 1218b: IMPURITY REGION, 1219a to 1219c: SIDEWALL, 1220a to 1220c: HIGH-CONCENTRATION IMPURITY REGION, 1221: RESIST MASK, 1222: FIRST INTERLAYER INSULATING FILM, 1223: SECOND INTERLAYER INSULATING FILM, 1225a to 1225e: WIRING, 1600: SUBSTRATE, 1601: ARITHMETIC CIRCUIT, 1602: ARITHMETIC CIRCUIT CONTROLLER, 1603: INSTRUCTION DECODER, 1604: INTERRUPT CONTROLLER, 1605: TIMING CONTROLLER, 1606: RESISTOR, 1607: RESISTOR CONTROLLER, 1608: BUS INTERFACE, 1609: ROM, 1620: ROM INTERFACE, 1621: CLK 1, 1622: CLK 2, 1700: GLASS SUBSTRATE, 1701: PEELING LAYER, 1702: BASE INSULATING FILM, 1703: SEMICONDUCTOR FILM, 1704: CRYSTALLINE SEMICONDUCTOR FILM, 1705 to 1707: SEMICONDUCTOR LAYER, 1708: GATE INSULATING FILM, 1709 to 1711: GATE ELECTRODE, 1712: RESIST, 1713: RESIST, 1716: LOW-CONCENTRATION IMPURITY REGION, 1717: LOW-CONCENTRATION IMPURITY REGION, 1718: RESIST, 1720: HIGH-CONCENTRATION IMPURITY REGION, 1721: INSULATING FILM, 1722 to 1724: SIDEWALL, 1726: RESIST, 1727: HIGH-CONCENTRATION IMPURITY REGION, 1728: HIGH-CONCENTRATION IMPURITY REGION, 1730: N-CHANNEL TFT, 1731: P-CHANNEL TFT, 1732: N-CHANNEL TFT, 1733: FIRST INTERLAYER INSULATING FILM, 1734: SECOND INTERLAYER INSULATING FILM, 1735 to 1739: WIRING, 1741: THIRD INTERLAYER INSULATING FILM, 1742: ANTENNA, 1745: PROTECTIVE LAYER, 1746: GROOVE, 1750: ADHESIVE AGENT 1751: SECOND SUBSTRATE, 1752: ADHESIVE AGENT, 1753: COVER MATERIAL, 2201: CASE, 2202: SUPPORTING STAND, 2203: DISPLAY PORTION, 2204: SPEAKER PORTION, 2205: VIDEO INPUT TERMINAL, 2211: CASE, 2212: DISPLAY PORTION, 2213: KEYBOARD, 2214: EXTERNAL CONNECTION PORT, 2215: POINTING MOUSE, 2221: CASE, 2222: DISPLAY PORTION, 2223: OPERATION KEY, 2231: CASE, 2232: DISPLAY PORTION, 2233: LENS, 2234: OPERATION KEY, 2235: SHUTTER, 2241: MAIN BODY, 2242: DISPLAY PORTION, 2243: CASE, 2244: EXTERNAL CONNECTION PORT, 2245: REMOTE CONTROL RECEIVING PORTION, 2246: IMAGE RECEIVING PORTION, 2247: BATTERY, 2248: AUDIO INPUT PORTION,

2249: OPERATION KEY, 2250: EYEPIECE PORTION, 2301: PASSPORT, 2302: WIRELESS IC TAG, 2311: WIRELESS IC TAG, 2312: READER, 2313: ANTENNA PORTION, 2501: LASER OSCILLATOR, 2502: CYLINDRICAL LENS ARRAY, 2503: MIRROR, 2504: CYLINDRICAL LENS, 2505: SLIT, 2506: PROJECTING LENS, 2507: CYLINDRICAL LENS, 2508: SEMICONDUCTOR FILM, 2509: SUBSTRATE, 2510: X STAGE, 2511: Y STAGE

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